

INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)				Docket Number (Optional) <b>DC4927</b>	Application Number <b>t be assigned</b>		
				Applicant(s) <b>Boisvert et al.</b>			
				Filing Date <b>to be assigned</b>	Group Art Unit <b>[7] 2 to-be-assigned</b>		
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	TELETYPE IF APPROPRIATE
KPP		<b>3,615,272</b>	<b>10/26/1971</b>	<b>Collins et al.</b>	<b>023</b>	<b>366</b>	
		<b>4,756,977</b>	<b>07/12/1988</b>	<b>Haluska et al.</b>	<b>428</b>	<b>704</b>	
		<b>5,446,088</b>	<b>08/29/1995</b>	<b>Haluska</b>	<b>524</b>	<b>588</b>	
		<b>6,022,814</b>	<b>02/08/2000</b>	<b>Mikoshiba et al.</b>	<b>438</b>	<b>789</b>	
✓		<b>6,231,989</b>	<b>05/15/2001</b>	<b>Chung et al.</b>	<b>428</b>	<b>447</b>	
FOREIGN PATENT DOCUMENTS							
REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
KPP	<b>WO 98/49721</b>	<b>5NOV1998</b>	<b>PCT</b>	<b>H01L</b>	<b>21/316</b>		
✓	<b>5-333553</b>	<b>19931217</b>	<b>Japan</b>	<b>G03F</b>	<b>7/075</b>	<b>✓</b>	
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
KPP		<b>JOURNAL OF MATERIALS CHEMISTRY; "Preparation of low density poly (methylsilsesquioxane)s for LSI interlayer dielectrics with low dielectric constant. Fabrication of Angstrom size pores prepared by baking trifluoropropylsilyl copolymers", Satoshi Mikoshiba and Shuzi Hayase, 1999, 9, 591-598.</b>					
EXAMINER <i>Klein Bey</i>		DATE CONSIDERED <b>8/17/03</b>					
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

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